

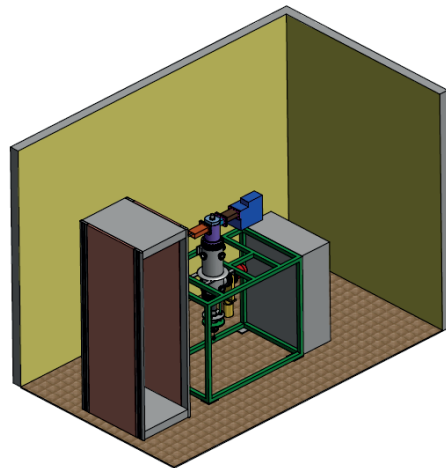
MWCVD-BASED MATERIAL LAYERS GROWTH FACILITY

Innovations and Benefits - The facility for material growth through Micro Wave Chemical Vapor Deposition can make use of ultrapure gases and grow electronic-grade diamond films. The facility can run 24 hours a day.

Uses - Growth of diamond films hundreds of micron thick, to be used as ionizing radiation and neutron detectors.

Past and Present Activities -

The facility is under advanced development at the ENEA Frascati Research Centre.



SERVIZI:

ENERGIA ELETTRICA

3X400V 50Hz +N +T @ 52A (Standard 63A).

Generatore MW..... 8 KW
 Heater..... 5 KW
 Gruppi di pompaggio..... 2 KW
 Diagnostiche di precesso 1 KW
 * Chiller raffreddamento
 liquido..... 5 KW

TOTALE MAX POTENZA ELETTRICA ASSORBITA 21 KW.

POTENZA MAX. TERMICA DISSIPATA IN AMBIENTE 1KW.

Liquido di raffreddamento o chiller
 15 L/mi @2,5 bar.

Aria compressa o Azoto N2..... 5 bar

Gas di processo flussi Massimi:

Idrogeno H2..... 1200 SCCM.
 Metano CH4..... 200SCCM
 Argon Ar..... a discrezione
 Azoto N2..... a discrezione

Characteristics: CUSTOM

Thanks to its flexibility, the service supplied by the facility can be adjusted to different needs and contexts